

Atty. Dkt. No. 039153-0306 (F0793)

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1-6. (Cancelled).

7. (Currently Amended) A method of manufacturing an integrated circuit, the method comprising:

providing a pattern of radiation via an LCD or LED assembly in response to a control signal from a computer, the computer generating the control signal ~~in response to image data stored in a database, the computer corresponding to the pattern, the control signal being generated by executing software to select a plurality of components, the components each being associated with individual image data, the individual image data being stored in a database, the computer component, and generating the control signal from the individual image data associated with the component components; and~~

performing a semiconductor fabrication process in accordance with the pattern of radiation.

8. (Original) The method of claim 7, further comprising:

providing a second pattern of radiation via the LCD or LED assembly; and

performing a second semiconductor fabrication process in accordance with the second pattern of radiation.

9. (Original) The method of claim 7, wherein the pattern is provided to a wafer in a step and repeat process.

10. (Currently Amended) The method of claim [[7]] 8, wherein the second pattern is representative of a metal layer associated with the integrated circuit.

11. (Original) The method of claim 7, wherein the pattern is representative of a structure associated with a transistor for the integrated circuit.

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12. (Currently Amended) The method of claim 7, wherein the individual component data is related to interconnect layers transistor structures.

13. (Original) The method of claim 7, wherein the integrated circuit is an ASIC.

14. (Original) The method of claim 7, wherein the pattern is provided via the LCD assembly.

15-20. (Cancelled).

21. (Currently Amended) A method of using a pattern generator for an integrated circuit fabrication system, the method comprising:

providing a pattern of radiation via an LCD assembly in response to a control signal from a computer, the computer generating the control signal in response to image data stored in a database, the image data including individual images associated with individual components, the computer executing software to select a component plurality of the individual components and generating the control signal from the associated individual images image data associated with the component; and

performing a semiconductor fabrication process in accordance with the pattern of radiation.

22. (Previously Presented) The method of claim 21, wherein the pattern is for an ASIC device.

23. (Previously Presented) The method of claim 22, wherein in the pattern generator further comprises:

means for providing a pattern of light;

means for controlling the means for providing, wherein the means for controlling selects the pattern; and

means for focusing the light on a wafer.

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24. (Previously Presented) The method of claim 15, wherein the image data are shapes representing component interconnects.

25. (Previously Presented) The method of claim 23, wherein the means for controlling includes a workstation executing a software program.

26. (Previously Presented) The method of claim 25, wherein the means for providing a pattern includes liquid crystals.

27. (Currently Amended) In a lithographic system for an integrated circuit fabrication process, the lithographic system including a computer and a configurable mask or reticle coupled to the computer, wherein the configurable mask or reticle allows light to be transmitted in a pattern controlled by a control signal from the computer, a method comprising:
providing a pattern of radiation via the configurable mask or reticle in response to a control signal from a computer, the computer generating the control signal in response to image data stored in a database, the image data including individual images associated with particular components, the computer executing software to select a number of the particular components component to generate the control signal in response to the individual images image data associated with the number of components component; and
performing a semiconductor fabrication process in accordance with the pattern of radiation.

28. (Previously Presented) The method of claim 27, wherein the configurable mask or reticle is an LCD or LED matrix.

29. (Previously Presented) The method of claim 27 wherein the image data includes ASIC information.

30. (Previously Presented) The method of claim 29, wherein the database is stored on a storage media.

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31. (Previously Presented) The method of claim 27, wherein the image data is related to transistor structures.

32. (Previously Presented) The method of claim 27, wherein the control signal is a video signal.

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Application No. 09/775,059